AZeci3007/Lor5b double layer resit recipe

Application

Only for sputtering

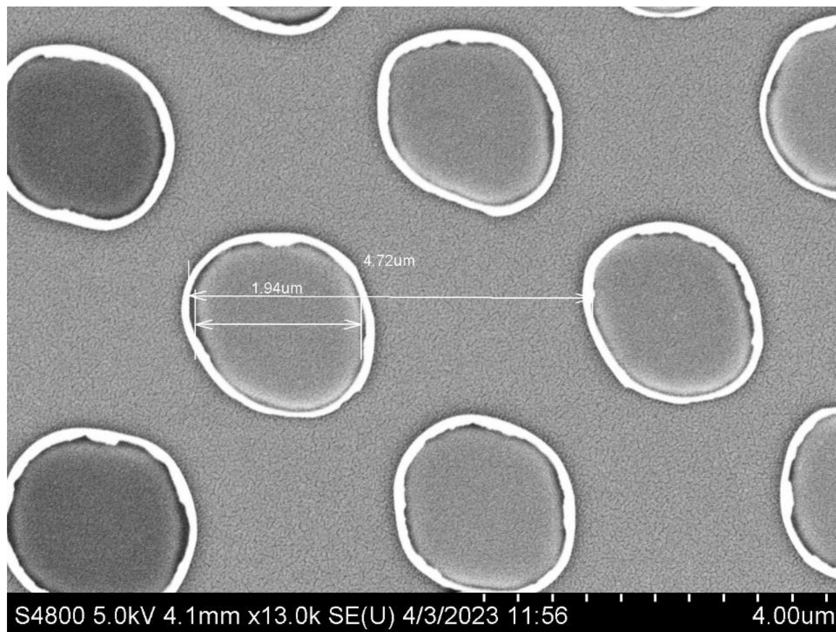
Tone	Positive
use	double layer resist for lift-off mask
reference	Data sheets available from kayakuam
spin coat and pre bake	Prebake: 200^{0}C for 5 minute First layer: Spin Lor5b @4000rpm 5minutes on hotplate @190^{0}C Second layer: Spin AzEci3007 @4000rpm 15minutes in oven @90^{0}C
Exposure	290 mJ/cm^2
development	45s MF21A
Limitations	Due to the undercut. The lines can't be any smaller then around 1um or they will fall off. If you want to do deposition afterwards you have to use evaporation, sputtering isn't suitable for this recipe.

Spincurves

See data sheet manufacturer

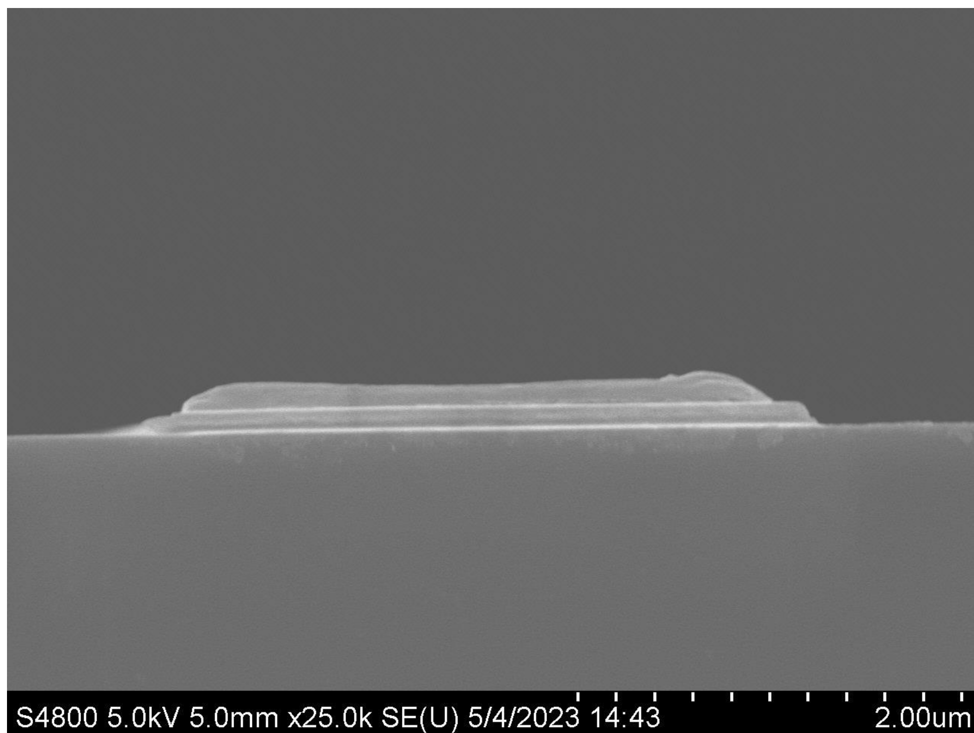
Results: SEM micrographs

After development:



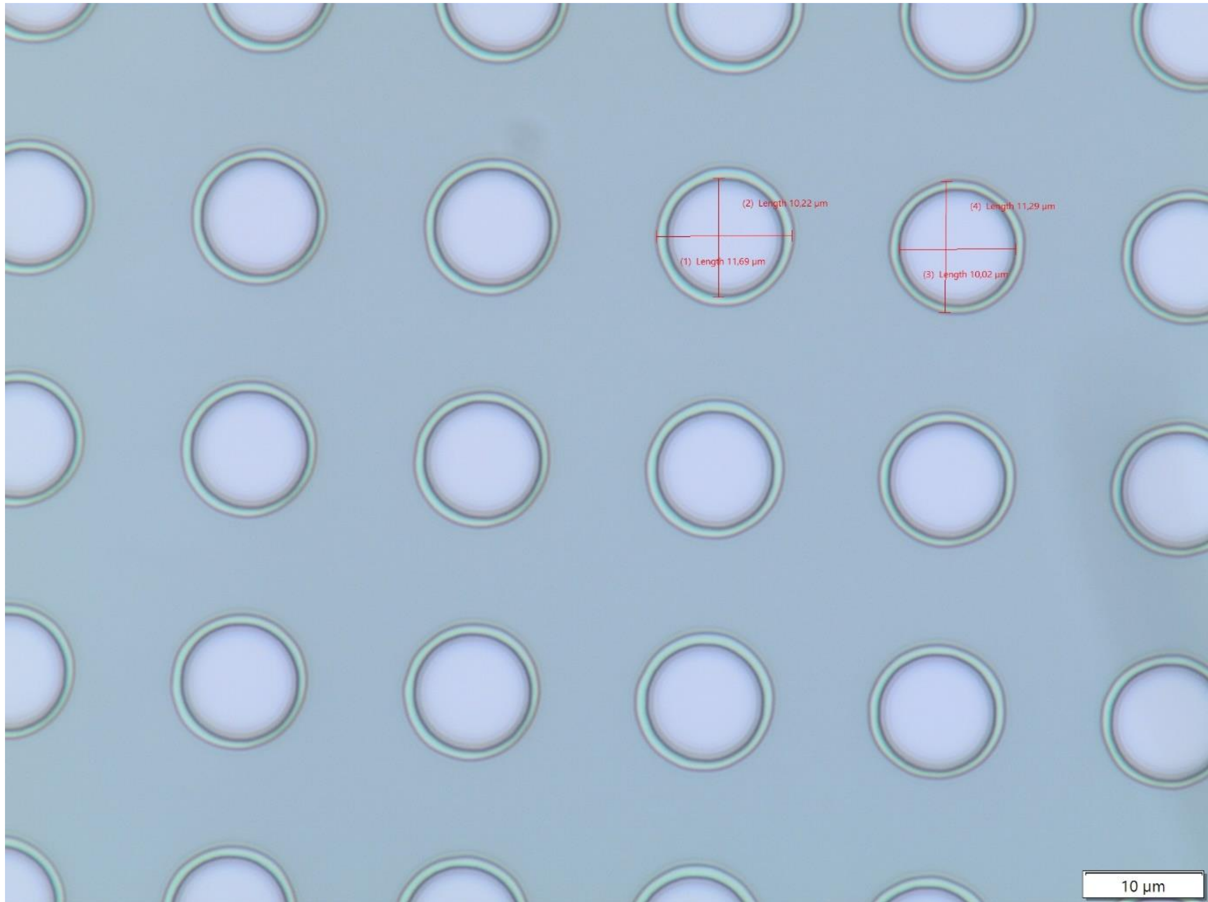
Deposition of 7nm Ti and 100nm Au
Liftoff in NMP for around 1 hour

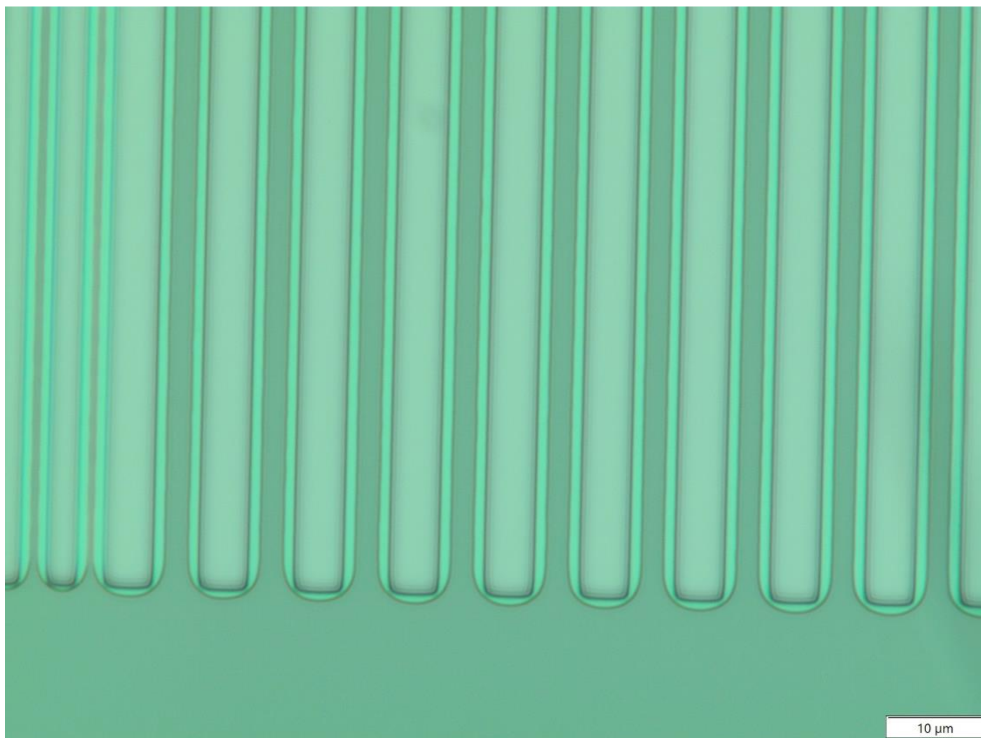
SEM inspection after lift-off



Optical microscope

After Development:





After Liftoff: